



F.Pérocheau, G.Frémont



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I. INTRODUCTION

In the years 2000, GANIL needed thin targets for FULIS experiment.

G. Frémont installed a laboratory here and started the production in 2004.

He benefited from the experience of a target laboratory near Strasbourg.



II. LABORATORY

Now, G.Frémont makes targets in a 50m2 room.







Target laboratory in GANIL

III. MECHANICAL PREPARATION

Rolling

Two rolling-mills



protection of foil by stainless-steel foils and/or by the atmosphere of the glove box

μm



Powder pressing



tablets are more easy to melt than powders



IV. CARBON SUBSTRATES PREPARATION

Carbon sublimation





V. MATERIALS DEPOSITION

Thin targets are mainly obtained here by evaporation





Depending on the material, we can choose particular configurations :

Small crucible for expensive material

Crucible heating by electron beam for high evaporation temperature







Target laboratory in GANIL





Direct heating of the material by electron beam for very high evaporation temperature





Target laboratory in GANIL

Evaporator for medium temperatures



Evaporator with electron beam (3 kW or 6 kW)



September 7th 2023



Evaporator for large surface



allows fabrication of detector parts



G.Frémont has experience of electro-deposition

Preparation of osmium targets with carbon backing Georges Fremont, Yvette Ngono-Ravache et al AIP Conf. Proc. 1962, 2018, 030002-1-030002-4

from OsCl₄ : Os on Cu foil -> Carbon deposition on Os -> Cu dissolution





VI. MATERIALS

G.F. knows how to fabricate targets using the following materials :

Al, Fe, Ni, Zn, Ge, Se, Ag, Sn, Au, Pb, PbS, Bi, Bi2O3 (in resistive crucible)

Mn, Mo (in cold crucible, heated by electron beam)

Mg, Ca, Ba, Gd, Yb (in small crucible heated by electron beam)

Os (by electro-deposition)





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VII. LABORATORY EVOLUTIONS

The new experimental devices in GANIL (S3, NFS ...) demand :

- the increase of target production volume (50 to 500 a year)
- the implemention of other materials





We need :

- new machines able to treat several substrates in one batch.
 > 15/day
- new machines for implementing high vaporisation temperature materials (Ta, Re...)
 -> sputtering
- protections against toxic materials (Pb, Ur, Th...)
 -> glove box
- protections for targets against O2 and H2O for sensitive materials (Ca, Ur ...)



and :

- chemical analyser (X fluorescence)
- thickness analyser (balance, alpha energy loss)
- two other technicians (one started recently)
- new rooms for installing these new machines



Thank you for your attention